



<b>[TA1] Sputtering Technologies</b>	
<b>Date / Time</b>	July 26 (Thu.), 2018 / 09:00-10:30
<b>Place</b>	Room A (#104~106)
<b>Session Chair(s)</b>	Junghoon Joo (Kunsan Nat'l Univ., Korea)

**TA1-1 [Invited]**

**09:00-09:30**

**PIC-MC Simulation Study of Rotational Magnetron Sputtering**

Andreas Pflug, Michael Siemers, Thomas Melzig, and Michael Vergöhl  
*Fraunhofer Inst. for Surface Engineering and Thin Films IST, Germany*

**TA1-2 [Invited]**

**09:30-10:00**

**ECR Plasma Enhanced Sputtering and Applications**

Seong Bong Kim<sup>1</sup>, Seungil Park<sup>1</sup>, Changho Yi<sup>1</sup>, Wan-Woo Park<sup>2</sup>, Jeong-Rak Lee<sup>2</sup>, Jae-Chul Do<sup>2</sup>, Woo-Jin Choi<sup>2</sup>,  
and Sung Haeng Cho<sup>3</sup>  
<sup>1</sup>NFRI, Korea, <sup>2</sup>AVACO Co., LTD., Korea, <sup>3</sup>ETRI, Korea

**TA1-3 [Invited]**

**10:00-10:30**

**Effect of Interface on the Structure and Ferro-Electric Property of Y-Doped HfO<sub>2</sub> Thin Films Prepared by Reactive Magnetron Co-Sputtering**

Jun Xu<sup>1</sup>, Yu Zhang<sup>1</sup>, Da-Yu Zhou<sup>1</sup>, Wen-Qi Lu<sup>1</sup>, Hang-Hang Wang<sup>1</sup>, and Chi Kyu Choi<sup>2</sup>  
<sup>1</sup>Dalian Univ. of Tech., China, <sup>2</sup>Jeju Nat'l Univ., Korea